



Patent
Attorney's Docket No. 027260-295

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

4/6/01
#9
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Re Patent Application of

Kazuya KAMON

Application No.: 09/320,946

Filed: May 26, 1999

For: PHOTOMASK, FABRICATION
METHOD OF PHOTOMASK, AND
FABRICATION METHOD OF
SEMICONDUCTOR INTEGRATED
CIRCUIT

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) Group Art Unit: 1756
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) Examiner: S. Mohamedulla
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PETITION FOR EXTENSION OF TIME

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

The following extension of time is requested to respond to Office Action dated December 5, 2000 and Advisory Action dated March 14, 2001:

one month to April 5, 2001; the extension fee is:

☐ \$55.00 (215) ☒ \$110.00 (115).

☐ The shortened statutory period has been reset by an Advisory Action dated

☒ An extension fee in the amount of \$ 110.00 is enclosed.

☐ Charge \$ _____ to Deposit Account No. 02-4800.

The Commissioner is hereby authorized to charge any appropriate fees under 37 C.F.R. §§ 1.16, 1.17 and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

Respectfully submitted,

BURNS, DOANE, SWECKER & MATHIS, L.L.P.

By:

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04/05/2001 JADD01 00000008 09320946
04 FC:115 110.00 OP

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Date: April 4, 2001

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